

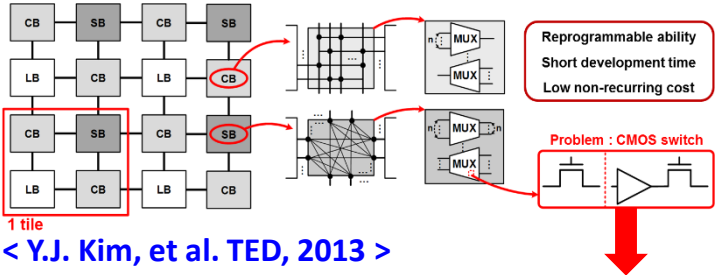
Island-Style Monolithic Three-Dimensional CMOS-Nanoelectromechanical Logic Circuits

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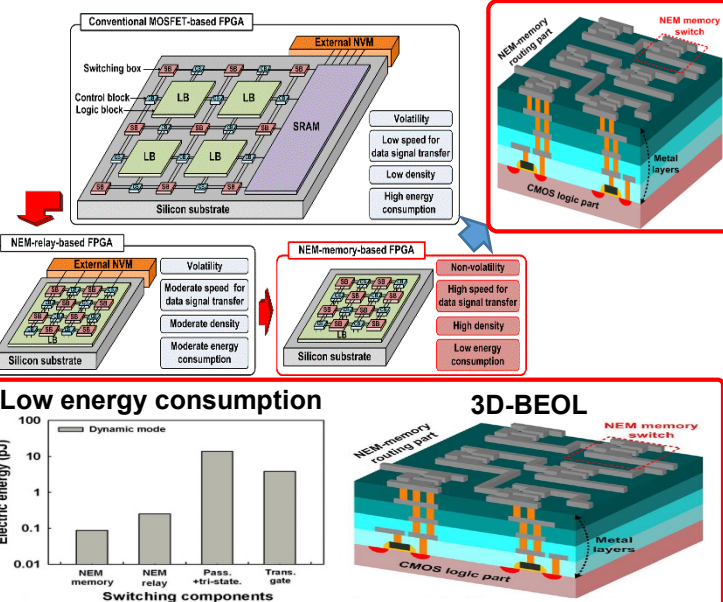
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Motivation

Limits of CMOS-only FPGAs



Merits of CMOS-NEM FPGAs

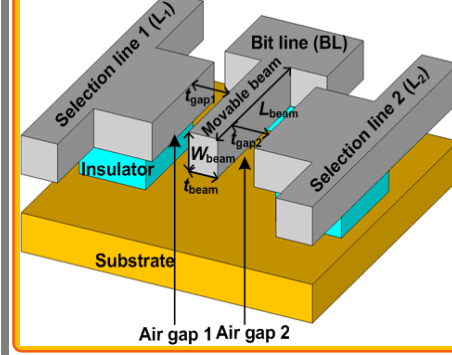


Ideas

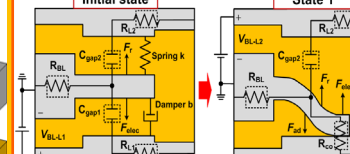
Basic structure of NEM switches

Operation of NEM memory switches

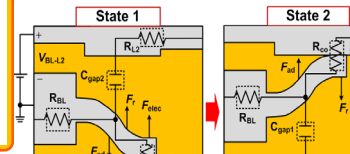
3-terminal NEM memory



Pull-in operation (V_p)



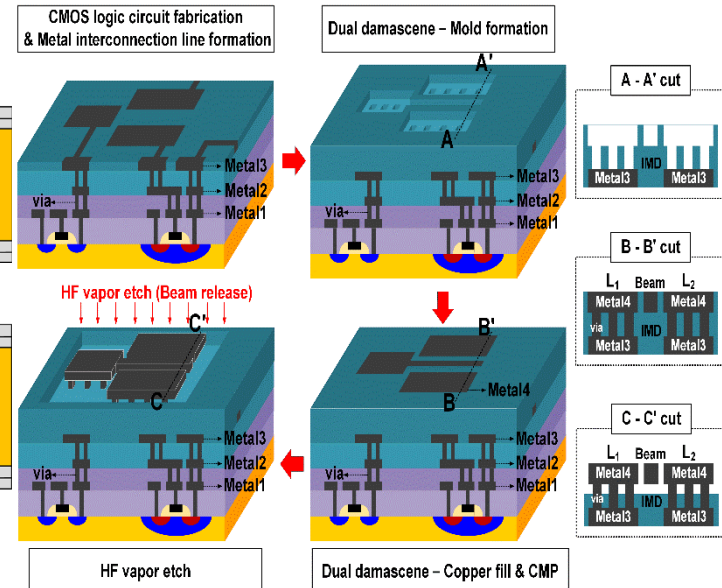
Release operation (V_r)



Zero voltage \rightarrow beam stiction

- \Rightarrow Nonvolatile & stable data signal path
- \Rightarrow Switching voltage (V_s) is determined by $\max(V_p, V_r)$

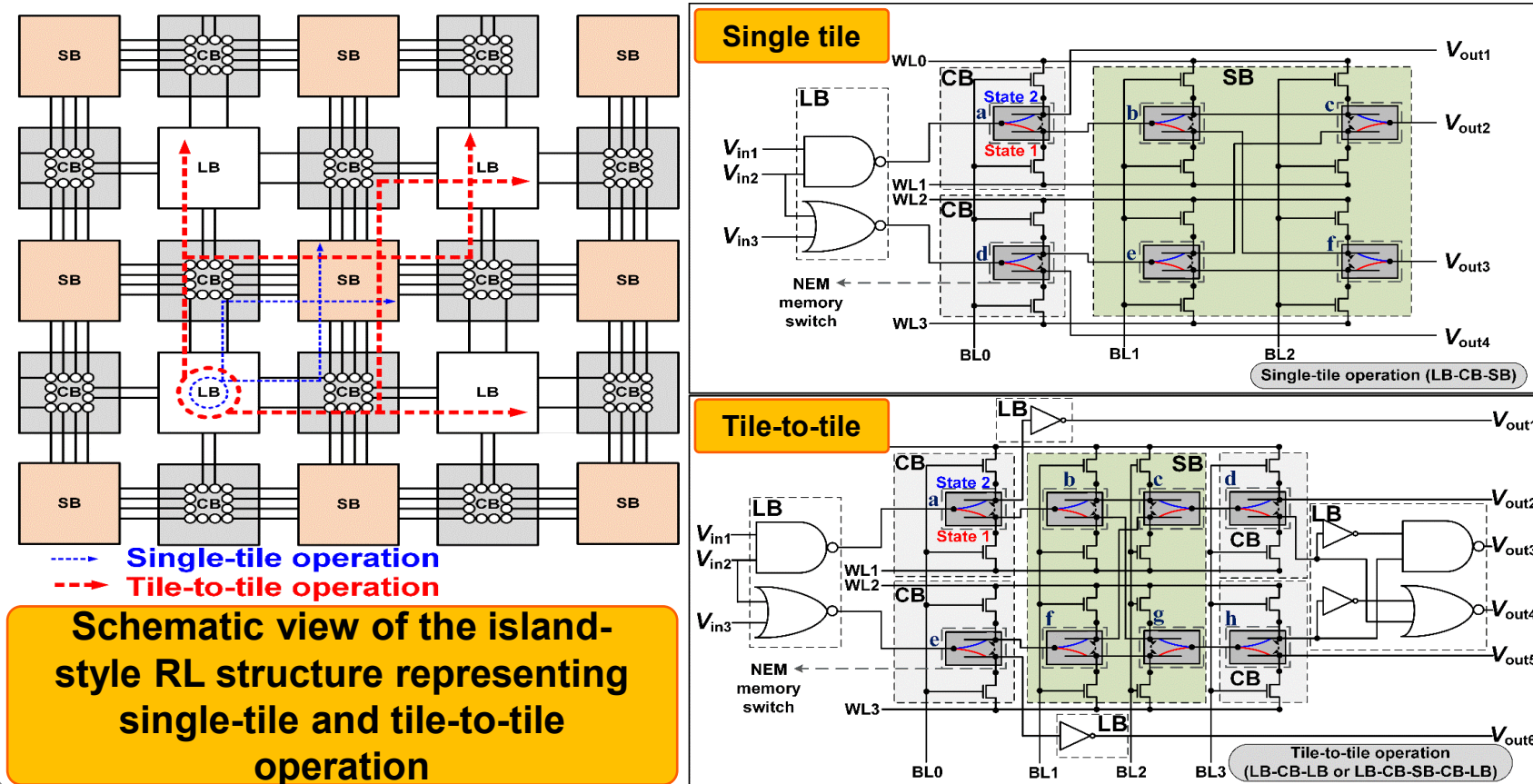
M3D integration process



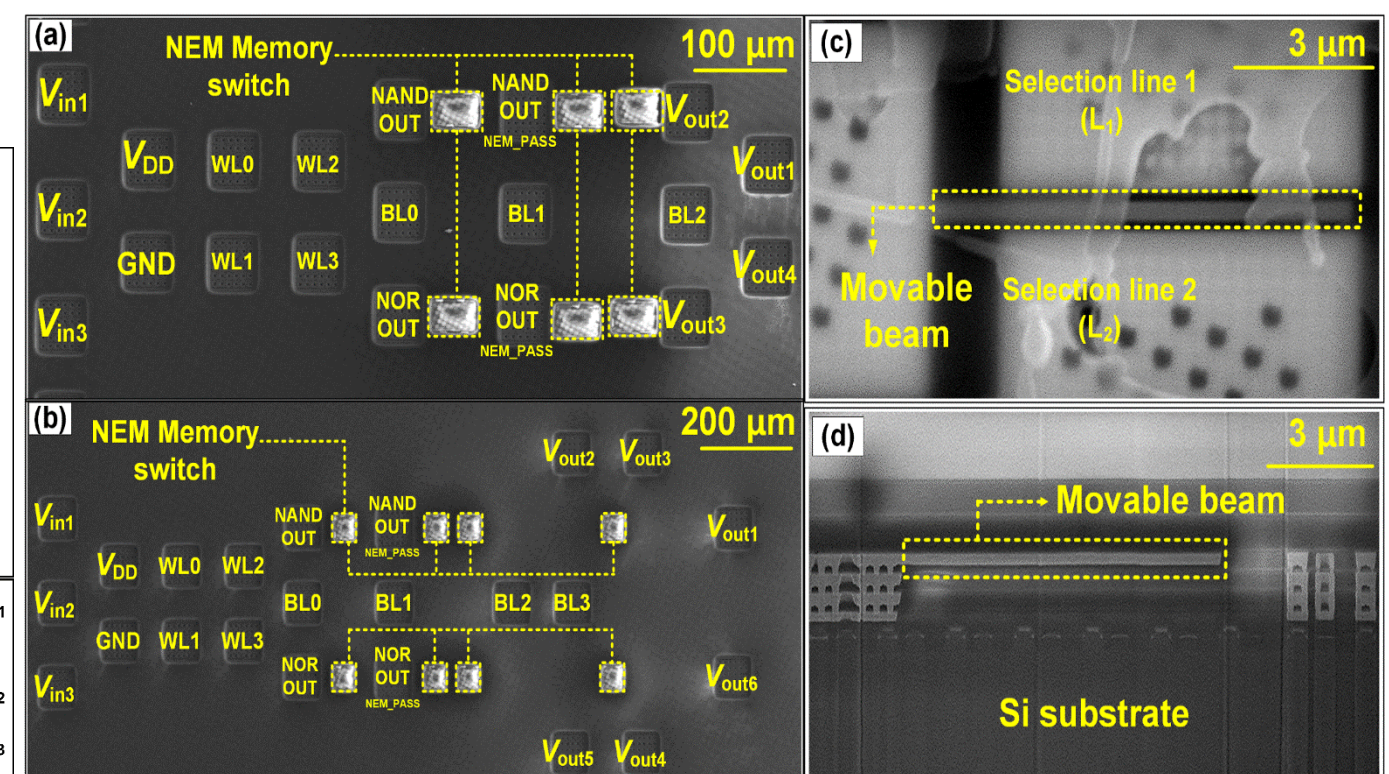
Method

Island style M3D CMOS-NEM RL circuits

\Rightarrow Consists of single tile and tile-to-tile CMOS-NEM RL circuits



Fabricated M3D CMOS-NEM RL circuit



Plan view of the fabricated M3D CMOS-NEM RL circuit for (a) single-tile operation and (b) tile-to-tile operation. (c) Plan and (d) cross-sectional view of the fabricated NEM memory switch

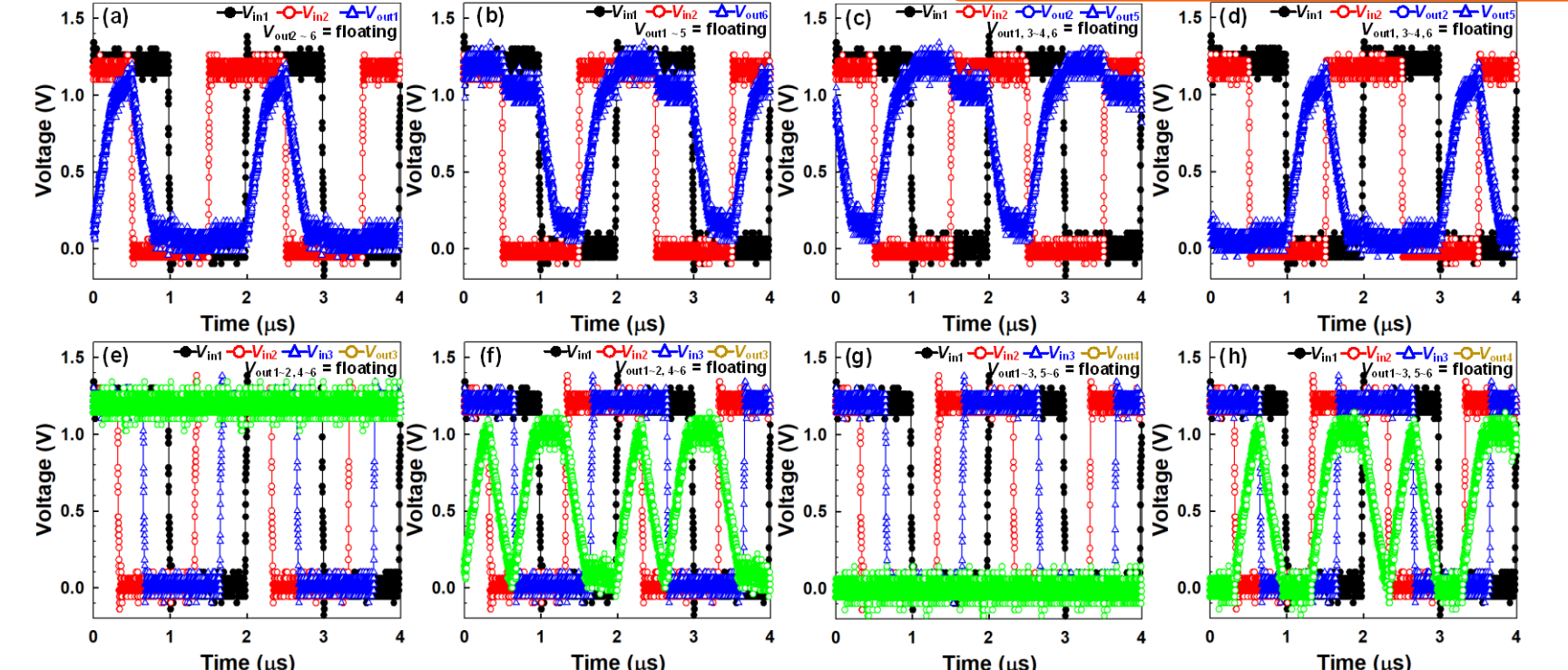
Experimental Result

\Rightarrow NEM memory switch operates under 1.2 V till $\sim 80^{\text{th}}$ cycle (maximum cycle : 260^{th})

\Rightarrow No difference between V_{out1} and V_{beam}

\checkmark Due to low resistive copper lines ($1.68 \mu\Omega\cdot\text{cm}$)

\Rightarrow NEM memory based RL circuits are successfully implemented satisfying the V_{DD} requirement of 65-nm CMOS technology node.



Current vs. voltage curves of the fabricated NEM memory switch

Measured input and out data signals of the fabricated M3D CMOS-NEM RL circuit for single-tile operation: (a) NAND output case and (b) NOR output case

Measured input and out data signals of the fabricated M3D CMOS-NEM RL circuit for tile-to-tile operation: (a) $V_{\text{in1}} \cdot V_{\text{in2}}$ output case, (b) $V_{\text{in2}} + V_{\text{in3}}$ output case, (c) NAND output case, (d) NOR output case, (e) $V_{\text{in1}} \cdot V_{\text{in2}}$ output case, (f) $V_{\text{in2}} + V_{\text{in3}}$ output case, (g) $V_{\text{in1}} \cdot V_{\text{in2}}$ output case, and (h) $V_{\text{in2}} + V_{\text{in3}}$ output case

Analysis

Comparison of RL circuit operation

Simulation was carried out by replacing CB & SB parts of the circuit.

Operation	Single-tile operation				Tile to tile operation			
	M3D CMOS-NEM (this work)	CMOS-only	CMOS-only	CMOS-only	M3D CMOS-NEM (this work)	CMOS-only	CMOS-only	CMOS-only
RL circuit	Pass gate	Transmission gate	Tri-state buffer	Tri-state buffer	Pass gate	Transmission gate	Tri-state buffer	Tri-state buffer
Max. freq. (GHz)	10.36	3.17	1.41	9.12	3.29	0.63	0.81	1.44
Power (μW)	3.42	5.26	10.52	188.78	82.81	323	175.03	752.42
Area (F^2)	480	1632	2784	3168	992	2528	4064	4576

\checkmark Proposed M3D CMOS-NEM RL circuits exhibit 4.6x higher chip density, 2.3x higher operation frequency and 9.3x lower power consumption than CMOS-only ones in tile-to-tile operation, tri-state buffer case.

Conclusion

\blacksquare NEM memory based FPGAs are implemented. NEM memory based FPGAs can achieve low operation voltage, low energy consumption, high signal transfer speed compared with CMOS only FPGAs.

\blacksquare Island style M3D CMOS-NEM RL circuits satisfying the V_{DD} requirement of the 65-nm CMOS technology node have been implemented and demonstrated for the first time.

\blacksquare NEM memory routing switches are vertically integrated over CMOS logic circuits by using the CMOS baseline BEOL process. The only difference is HF vapor etching used to release the NEM structures.

\blacksquare It is predicted that proposed M3D CMOS-NEM RL circuits will exhibit 4.6x higher chip density, 2.3x higher operation frequency and 9.3x lower power consumption than CMOS-only ones (tri-state buffer case) for tile-to-tile operation.